

Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 128375	APPLICATION NO. 10/582,268
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT(S) Yasufumi NISHII et al.	
				FILING DATE June 9, 2006	
U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number	Date	Name	
	1	2005/0190455 A1	09/01/2005	ROSTALSKI et al.	
	2	2005/0117224 A1	06/02/2005	SHAFFER et al.	
	3	2002/0163629 A1	11/07/2002	SWITKES et al.	
	4	2003/0030916 A1	02/13/2003	SUENAGA	
	5	2005/0141098 A1	06/30/2005	SCHUSTER	
	6	2004/0000627 A1	01/01/2004	SCHUSTER	
	7	2005/0030506 A1	02/10/2005	SCHUSTER	
	8	2005/0217135 A1	10/06/2005	O'DONNELL et al.	
	9	2005/0217137 A1	10/06/2005	SMITH et al.	
	10	2005/0217703 A1	10/06/2005	O'DONNELL	
	11	2004/0075895 A1	04/22/2004	LIN	
	12	2004/0118184 A1	06/24/2004	VIOLETTE	
	13	2004/0125351 A1	07/01/2004	KRAUTSCHIK	
	14	2004/0180294 A1	09/16/2004	BABA-ALI et al.	
	15	2004/0169924 A1	09/02/2004	FLAGELLO et al.	
	16	2004/0227923 A1	11/18/2004	FLAGELLO et al.	
	17	2003/0174408 A1	09/18/2003	ROSTALSKI et al.	
	18	2004/0180299 A1	09/16/2004	ROLLAND et al.	
	19	2004/0109237 A1	06/10/2004	EPPLER et al.	
	20	2004/0257544 A1	12/23/2004	VOGEL et al.	
	21	2004/0263808 A1	12/30/2004	SEWELL	
	22	2005/0036183 A1	02/17/2005	YEO et al.	
	23	2005/0036184 A1	02/17/2005	YEO et al.	
	24	2005/0037269 A1	02/17/2005	LEVINSON	
	25	2005/0036213 A1	02/17/2005	MANN et al.	
	26	2004/0224265 A1	11/11/2004	ENDO et al.	
	27	2004/0224525 A1	11/11/2004	ENDO et al.	
	28	2005/0046934 A1	03/03/2005	HO et al.	
	29	2005/0048223 A1	03/03/2005	PAWLOSKI et al.	
	30	2004/0253547 A1	12/16/2004	ENDO et al.	

Date: October 19, 2006

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /ML/

	31	2004/0253548 A1	12/16/2004	ENDO et al.
	32	2005/0068639 A1	03/31/2005	PIERRAT et al.
	33	2005/0073670 A1	04/07/2005	CARROLL
	34	2005/0084794 A1	04/21/2005	MEAGLEY et al.
	35	2005/0094116 A1	05/05/2005	FLAGELLO et al.
	36	2005/0100745 A1	05/12/2005	LIN et al.
	37	2004/0136494 A1	07/15/2004	LOF et al.
	38	2004/0160582 A1	08/19/2004	LOF et al.
	39	2004/0165159 A1	08/26/2004	LOF et al.
	40	2004/0207824 A1	10/21/2004	LOF et al.
	41	2004/0211920 A1	10/28/2004	MARIA DERKSEN et al.
	42	2005/0036121 A1	02/17/2005	HOOGENDAM et al.
	43	2004/0169834 A1	09/02/2004	RICHTER et al.
	44	2004/0259040 A1	12/23/2004	ENDO et al.
	45	2004/0114117 A1	06/17/2004	BLEEKER
	46	2004/0259008 A1	12/23/2004	ENDO et al.
	47	2005/0110973 A1	05/26/2005	STREEFKERK et al.
	48	2005/0122497 A1	06/09/2005	LYONS et al.
	49	2004/0119954 A1	06/24/2004	KAWASHIMA et al.
	50	2005/0185269 A1	08/25/2005	EPPLÉ et al.
	51	2005/0225737 A1	10/13/2005	WEISSENRIEDER et al.
	52	2005/0132914 A1	06/23/2005	MULKENS et al.
	53	2005/0134815 A1	06/23/2005	VAN SANTEN et al.
	54	2005/0147920 A1	07/07/2005	LIN et al.
	55	2005/0145803 A1	07/07/2005	HAKEY et al.
	56	2005/0146694 A1	07/07/2005	TOKITA
	57	2005/0146695 A1	07/07/2005	KAWAKAMI
	58	2005/0153424 A1	07/14/2005	COON
	59	2005/0190435 A1	09/01/2005	SHAFFER et al.
	60	2005/0158673 A1	07/21/2005	HAKEY et al.
	61	2005/0164502 A1	07/28/2005	DENG et al.
	62	2005/0270505 A1	12/08/2005	SMITH
	63	2005/0174549 A1	08/11/2005	DUINEVELD et al.
	64	2005/0175940 A1	08/11/2005	DIERICHS
	65	2005/0042554 A1	02/24/2005	DIERICHS et al.
	66	2005/0205108 A1	09/22/2005	CHANG et al.
	67	2005/0213061 A1	09/29/2005	HAKEY et al.
	68	2005/0213072 A1	09/29/2005	SCHENKER et al.
	69	2005/0219499 A1	10/06/2005	MARIA ZAAL et al.

Date: October 19, 2006

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /ML/

	70	2005/0219482 A1	10/06/2005	BASELMANS et al.
	71	2005/0219481 A1	10/06/2005	COX et al.
	72	2005/0024609 A1	02/03/2005	DE SMIT et al.
	73	2005/0231694 A1	10/20/2005	KOLESNYCHENKO et al.
	74	2005/0237501 A1	10/27/2005	FURUKAWA et al.
	75	2005/0245005 A1	11/03/2005	BENSON
	76	2005/0243292 A1	11/03/2005	BASELMANS et al.
	77	2005/0253090 A1	11/17/2005	GAU et al.
	78	2005/0007569 A1	01/13/2005	STREEFKERK et al.
	79	2005/0259232 A1	11/24/2005	STREEFKERK et al.
	80	2004/0233405 A1	11/25/2004	KATO et al.
	81	2005/0259233 A1	11/24/2005	STREEFKERK et al.
	82	2005/0007570 A1	01/13/2005	STREEFKERK et al.
	83	2005/0264778 A1	12/01/2005	LOF et al.
	84	2005/0002004 A1	01/06/2005	KOLESNYCHENKO et al.
	85	2005/0030498 A1	02/10/2005	MULKENS
	86	2004/0263809 A1	12/30/2004	NAKANO
	87	2005/0018155 A1	01/27/2005	COX et al.
	88	2005/0018156 A1	01/27/2005	MULKENS et al.
	89	2005/0030497 A1	02/10/2005	NAKAMURA
	90	2005/0134817 A1	06/23/2005	NAKAMURA
	91	2005/0145265 A1	07/07/2005	RAVKIN et al.
	92	2005/0041225 A1	02/24/2005	SENGERS et al.
	93	2005/0046813 A1	03/03/2005	STREEFKERK et al.
	94	2005/0048220 A1	03/03/2005	MERTENS et al.
	95	2005/0030511 A1	02/10/2005	AUER-JONGEPIER et al.
	96	2005/0078286 A1	04/14/2005	DIERICHS et al.
	97	2005/0078287 A1	04/14/2005	SENGERS et al.
	98	2005/0233081 A1	10/20/2005	TOKITA
	99	2005/0052632 A1	03/10/2005	MIYAJIMA
	100	2005/0088635 A1	04/28/2005	HOOGENDAM et al.
	101	2005/0259236 A1	11/24/2005	STRAAIJER
	102	2005/0094114 A1	05/05/2005	STREEFKERK et al.
	103	2005/0094119 A1	05/05/2005	LOOPSTRA et al.
	104	2005/0074704 A1	04/07/2005	ENDO et al.
	105	2005/0128445 A1	06/16/2005	HOOGENDAM et al.
	106	2005/0179877 A1	08/18/2005	MULKENS et al.
	107	2005/0174550 A1	08/11/2005	STREEFKERK et al.
	108	2005/0263068 A1	12/01/2005	HOOGENDAM et al.

Date: October 19, 2006

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /ML/

	109	2005/0106512 A1	05/19/2005	ENDO et al.
	110	2005/0117135 A1	06/02/2005	VERHOEVEN et al.
	111	2005/0175776 A1	08/11/2005	STREEFKERK et al.
	112	2005/0122505 A1	06/09/2005	MIYAJIMA
	113	2005/0146693 A1	07/07/2005	OHSAKI
	114	2005/0136361 A1	06/23/2005	ENDO et al.
	115	2005/0259234 A1	11/24/2005	HIRUKAWA et al.
	116	2006/0139614 A1	06/29/2006	OWA et al.
	117	4,346,164	08/24/1982	TABARELLI et al.
	118	4,480,910	11/06/1984	TAKANASHI et al.
	119	5,825,043	10/20/1998	SUWA
	120	5,715,039	02/03/1998	FUKUDA et al.

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation
	121	JP A 57-153433	09/22/1982	JAPAN	X	X
	122	JP A 58-202448	11/25/1983	JAPAN	X	X
	123	JP A 59-019912	02/01/1984	JAPAN	X	X
	124	JP A 62-065326	03/24/1987	JAPAN	X	X
	125	JP A 63-157419	06/30/1988	JAPAN	X	X
	126	JP A 04-305915	10/28/1992	JAPAN	X	X
	127	JP A 04-305917	10/28/1992	JAPAN	X	X
	128	JP A 05-062877	03/12/1993	JAPAN	X	X
	129	JP A 07-220990	08/18/1995	JAPAN	X	X
	130	JP A 10-303114	11/13/1998	JAPAN	X	X
	131	JP A 10-340846	12/22/1998	JAPAN	X	X
	132	JP A 11-176727	07/02/1999	JAPAN	X	X
	133	JP A 2000-058436	02/25/2000	JAPAN	X	X
	134	JP A 06-124873	05/06/1994	JAPAN	X	X
	135	JP A 08-316125	11/29/1996	JAPAN	X	X
	136	WO 2004/019128 A2	03/04/2004	WIPO		
	137	WO 2002/091078 A1	11/14/2002	WIPO		
	138	WO 2004/077154 A2	09/10/2004	WIPO		
	139	WO 2003/077037 A1	09/18/2003	WIPO		
	140	WO 2004/081666 A1	09/23/2004	WIPO		
	141	WO 2005/001432 A2	01/06/2005	WIPO		
	142	WO 2004/093159 A2	10/28/2004	WIPO		
	143	WO 2004/090634 A2	10/21/2004	WIPO		
	144	WO 2004/090633 A2	10/21/2004	WIPO		

Date: October 19, 2006

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /ML/

	145	WO 2004/092833 A2	10/28/2004	WIPO		
	146	WO 2004/093160 A2	10/28/2004	WIPO		
	147	WO 2004/090577 A2	10/21/2004	WIPO		
	148	WO 2004/092830 A2	10/28/2004	WIPO		
	149	WO 2004/093130 A2	10/28/2004	WIPO		
	150	WO 2004/095135 A2	11/04/2004	WIPO		
	151	WO 2005/003864 A2	01/13/2005	WIPO		
	152	WO 2005/006026 A2	01/20/2005	WIPO		
	153	WO 2005/008339 A2	01/27/2005	WIPO		
	154	WO 2005/013008 A2	02/10/2005	WIPO		
	155	WO 2005/017625 A2	02/24/2005	WIPO		
	156	WO 2005/015283 A1	02/17/2005	WIPO		
	157	WO 2005/019935 A2	03/03/2005	WIPO		
	158	WO 2005/024325 A2	03/17/2005	WIPO		
	159	WO 2005/022266 A2	03/10/2005	WIPO		
	160	WO 2005/024517 A2	03/17/2005	WIPO		
	161	WO 2005/034174 A2	04/14/2005	WIPO		
	162	WO 2004/055803 A1	07/01/2004	WIPO		
	163	WO 2004/057589 A1	07/08/2004	WIPO		
	164	WO 2004/057590 A1	07/08/2004	WIPO		
	165	WO 2005/054953 A2	06/16/2005	WIPO		
	166	WO 2005/054955 A2	06/16/2005	WIPO		
	167	WO 2005/062128 A2	07/07/2005	WIPO		
	168	WO 2005/059617 A2	06/30/2005	WIPO		
	169	WO 2005/059654 A1	06/30/2005	WIPO		
	170	WO 2005/059645 A2	06/30/2005	WIPO		
	171	WO 2005/059618 A2	06/30/2005	WIPO		
	172	WO 2005/064405 A2	07/14/2005	WIPO		
	173	WO 2005/064400 A2	07/14/2005	WIPO		
	174	WO 2005/069055 A2	07/28/2005	WIPO		
	175	WO 2005/069081 A2	07/28/2005	WIPO		
	176	WO 2005/071491 A2	08/04/2005	WIPO		
	177	WO 2005/074606 A2	08/18/2005	WIPO		
	178	WO 2005/076084 A1	08/18/2005	WIPO		
	179	WO 2005/081067 A1	09/01/2005	WIPO		
	180	WO 2005/081030 A1	09/01/2005	WIPO		
	181	WO 2005/069078 A1	07/28/2005	WIPO		
	182	WO 2005/050324 A2	06/02/2005	WIPO		

Date: October 19, 2006

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /ML/

	183	WO 2005/098504 A1	10/20/2005	WIPO		
	184	WO 2005/098505 A1	10/20/2005	WIPO		
	185	WO 2005/098506 A1	10/20/2005	WIPO		
	186	WO 2005/106589 A1	11/10/2005	WIPO		
	187	WO 2005/111722 A2	11/24/2005	WIPO		
	188	WO 2005/111689 A2	11/24/2005	WIPO		
	189	WO 2005/119368 A2	12/15/2005	WIPO		
	190	WO 2005/119369 A1	12/15/2005	WIPO		
	191	WO 2005/001572 A2	01/06/2005	WIPO		
	192	WO 2005/048328 A1	05/26/2005	WIPO		
	193	WO 2005/062351 A1	07/07/2005	WIPO		
	194	DD 221 563 A1	04/24/1985	GERMANY		X
	195	DD 224 448 A1	07/03/1985	GERMANY		X

OTHER DOCUMENTS

Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)
	196	Lin, B.J. "Semiconductor Foundry, Lithography, and Partners." Proceedings of SPIE, Vol. 4688, pp. 11 - 24, 2002.
	197	Switkes, M., et al. "Resolution Enhancement of 157nm Lithography by Liquid Immersion." Proceedings of SPIE, Vol. 4691, pp. 459 - 465, 2002.
	198	Switkes, M., et al. "Resolution Enhancement of 157nm Lithography by Liquid Immersion." J. Microlith., Microfab., Microsyst., Vol. 1, No. 3, pp. 1 - 4, 2002.
	199	Owa, Soichi, et al. "Nikon F2 Exposure Tool," slides 1 - 25, 3 rd 157nm Symposium, September 4, 2002.
	200	Owa, Soichi. "Immersion Lithography," slides 1 - 24, Immersion Lithography Workshop, December 11, 2002.
	201	Owa, Soichi, et al. "Immersion Lithography; its Potential Performance and Issues." Proceedings of SPIE, Vol. 5040, pp. 724 - 733, 2003.
	202	Owa, Soichi, et al. "Potential Performance and Feasibility of Immersion Lithography," slides 1 - 33, NGL Workshop 2003, July 10, 2003.
	203	Owa, Soichi, et al. "Update on 193nm Immersion Exposure Tool," slides 1 - 38, Immersion Workshop 2004, January 27, 2004.
	204	Owa, Soichi, et al. "Update on 193nm Immersion Exposure Tool," slides 1 - 51, Litho Forum, January 28, 2004.

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DATE CONSIDERED
07/03/2008

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